Semiconductor Ptfe Wafer Carrier 8 Inch Wet Cleaning Hf Resistant Etching Cassette

Item Number: PL-CP82

Introduction

Optimize semiconductor processing with this premium PTFE 8 inch wafer carrier designed for high-purity wet cleaning and HF etching applications. Our industrial-grade fluoropolymer cassettes ensure maximum chemical resistance, superior durability, and precise handling for sensitive cleanroom production environments.

Learn More

Application	Description	Key Benefit
Silicon Wafer Etching	Handling wafers during the removal of sacrificial layers using HF-based chemistries.	Complete resistance to acid attack ensures carrier longevity.
RCA Cleaning Process	Supporting wafers through multiple stages of organic and ionic contaminant removal.	Material purity prevents re-contamination of cleaned surfaces.
CMP Post-Cleaning	Transporting wafers through cleaning brushes and chemical baths after planarization.	Low particle shedding maintains extremely low defect counts.
Photoresist Stripping	Utilizing aggressive solvents to remove light-sensitive coatings after lithography.	Chemical inertness prevents material degradation in solvent baths.
Solar Cell Fabrication	Supporting large-scale substrate processing in high-acid environments for PV cells.	Durability in high-volume production reduces replacement costs.
MEMS Manufacturing	Managing delicate micro-electromechanical systems during complex wet release steps.	Precise slot alignment prevents mechanical damage to structures.
Analytical Sampling	Using the carrier as a substrate holder for high-purity trace metal analysis.	Ultra-low background levels ensure accurate laboratory results.

Feature Category	Technical Details for PL-CP82
Product Identification	PL-CP82 Series Custom Wafer Carrier
Primary Material	High-Purity Virgin PTFE (Polytetrafluoroethylene)
Wafer Size Compatibility	Standard 8-inch (200mm) / Fully Customizable diameters
Configuration Type	Single-wafer (individual) or Multi-slot available
Fabrication Method	100% Precision CNC Machining (No molding residues)
Temperature Range	-200°C to +260°C (-328°F to +500°F)
Chemical Compatibility	Universal (HF, HCl, H2SO4, KOH, Acetone, etc.)
Surface Roughness	Customizable based on specific cleanroom requirements
Slot Pitch / Depth	Tailored to client-specific process parameters
Handle/Interface	Custom robotic pick-up points or manual grip options

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Feature Category	**Technical Details for PL-CP82**	
Dimensional Accuracy	High-precision tolerance control per industrial standards	